

L Number	Hits	Search Text	DB	Time stamp
1	32	"5817562"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 20:20
2	4	"5861190"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 20:20
3	9	"6323519"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 20:20
4	2	"6368984"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 20:21
5	4	"6136728"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 20:21
6	3	"6245689"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 20:21
7	6	"6144071"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 20:22
8	7	"6211003"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 20:22
9	3	"6232187"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 20:27
10	5	"5707889"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 20:27
11	12	"6040216"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 20:27
12	2	"6252296"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 20:28

13	4	"6246091"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 20:28
14	91	"5817562" or "5861190" or "6323519" or "6368984" or "6136728" or "6245689" or "6144071" or "6211003" or "6040216" or "6232187" or "5707889" or "6252296" or "6246091"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 20:29
15	7	("5817562" or "5861190" or "6323519" or "6368984" or "6136728" or "6245689" or "6144071" or "6211003" or "6040216" or "6232187" or "5707889" or "6252296" or "6246091") and oxynitride and ((concentration\$2 or peak\$2) with nitrogen)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 21:21
16	318	(amorphous with (silicon or polysilicon)) and oxynitride and ((concentration\$2 or peak\$2) with nitrogen)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 21:22
18	0	((amorphous with (silicon or polysilicon) with (heat\$4 or anneal\$4)) and oxynitride and ((concentration\$2 or peak\$2) with nitrogen)) and ((sidewall\$4 or (side adj wall\$2) or spacer\$2) with (l adj shape\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 21:25
19	30	((amorphous with (silicon or polysilicon) with (heat\$4 or anneal\$4)) and oxynitride and ((concentration\$2 or peak\$2) with nitrogen)) and ((sidewall\$4 or (side adj wall\$2) or spacer\$2) with shape\$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 21:26
17	134	(amorphous with (silicon or polysilicon) with (heat\$4 or anneal\$4)) and oxynitride and ((concentration\$2 or peak\$2) with nitrogen)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 21:33
20	104	((amorphous with (silicon or polysilicon) with (heat\$4 or anneal\$4)) and oxynitride and ((concentration\$2 or peak\$2) with nitrogen)) not (((amorphous with (silicon or polysilicon) with (heat\$4 or anneal\$4)) and oxynitride and ((concentration\$2 or peak\$2) with nitrogen)) and ((sidewall\$4 or (side adj wall\$2) or spacer\$2) with shape\$4))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/05/21 21:33